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Plasma treatment on carbon nanowalls grown by microwave PECVD

Won Seok Choi¹, Yeun-Ho Joung¹, Feel-Soon Kang¹ and Hyun Suk Hwang² ¹Hanbat National University, Republic of Korea ²Seoil University, Republic of Korea

In this study, the effects of post-plasma treatment on synthesized carbon nanowalls (CNWs) grown with a microwave were investigated. CNWs were synthesized by microwave plasma enhanced chemical vapor deposition (PECVD), employing a mixture of CH_4 and H_2 gases. The plasma treatment was done in different plasma environments (O_2 and H_2) but under the same condition of synthesized CNWs. Raman spectroscopy, field emission scanning electron microscopy (FE-SEM), energy dispersive X-ray spectroscopy (EDS), and fourier transform infrared spectroscopy (FT-IR) were used to analyze the effects of the post-plasma treatment on the synthesized CNWs. After the H_2 post-plasma treatment, no significant changes in the appearance and characteristics of the CNWs were observed. After the O_2 post-plasma treatment, on the other hand, the CNWs were etched at a rate of 18.05 nm/sec. The Raman analysis confirmed, however, that the structural changes in the CNWs caused by the O_2 post-plasma treatment were insignificant.

Biography

Won Seok Choi received his PhD degree from Sungkyunkwan University, Seoul, Korea,in 2006. After his PhD, he has continued his research at Center for Advanced Plasma Science and Technology as a postdoc fellow. In 2007, he joined the faculty of the Department of Electrical Engineering, Hanbat National University, Daejeon, Korea. His research interests include synthesis and application of nanomaterials.

wschoi@hanbat.ac.kr

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